

	Hits	Search Text	DBs
1	7	(mask\$3 or photomask or reticle) and ((project\$4 near9 lens)) and (((final or bottom) near5 lens near6 element) same ((close near9 proximit\$4) or distance or adjacent) same (sample or substrate or wafer or photosensitive or photoresist or resist)) and (expos\$4 or illuminant\$4 or irradiat\$4 or imag\$3) and ((lens or (refractive near26 slab) or (projection near6 lens near6 element)) same (adjacent or (close near6 proximit\$5) or abutt\$5) same (wafer or photoresist or substrate or photosensitive or sample)) and ((lens or (refractive near5 slab) or (projec\$5 near5 lens\$4 near4 element)) near16 ((refractive near6 index) or (index near4 refraction)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
2	40	(((layout near8 object) or pattern\$4) same (mask\$3 or photomask or reticle)) and ((project\$4 near9 lens) same ((close near9 proximit\$4) or contact or vicinit\$3 or depress\$4 or touch\$3 or indent\$\$) same (sample or substrate or wafer or photosensitive or photoresist or resist)) and (expos\$4 or illuminant\$4 or irradiat\$4 or imag\$3) and ((lens or (refractive near26 slab) or (projection near6 lens near6 element)) same (adjacent or (close near6 proximit\$5) or abutt\$5) same (wafer or photoresist or substrate or photosensitive or sample)) and ((lens or (refractive near5 slab) or (projec\$5 near5 lens\$4 near4 element)) near29 ((refractive near6 index) or (index near4 refraction)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
3	35	(((layout near8 object) or pattern\$4) same (mask\$3 or photomask or reticle)) and ((project\$4 near9 lens) same ((close near9 proximit\$4) or contact or touch\$3) same (sample or substrate or wafer or photosensitive or photoresist or resist)) and (expos\$4 or illuminant\$4 or irradiat\$4 or imag\$3) and ((lens or (refractive near26 slab) or (projection near6 lens near6 element)) same (adjacent or (close near6 proximit\$5) or abutt\$5) same (wafer or photoresist or substrate or photosensitive or sample)) and ((lens or (refractive near5 slab) or (projec\$5 near5 lens\$4 near4 element)) near29 ((refractive near6 index) or (index near4 refraction)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
4	5	L2 NOT L3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
5	0	250/492.22.ccls. and (((layout near8 object) or pattern\$4) same (mask\$3 or photomask or reticle)) and ((project\$4 near9 lens) same ((close near9 proximit\$4) or contact or vicinit\$3 or depress\$4 or touch\$3 or indent\$\$) same (sample or substrate or wafer or photosensitive or photoresist or resist)) and (expos\$4 or illumiant\$4 or irradiat\$4 or imag\$3) and ((lens or (refractive near26 slab) or (projection near6 lens near6 element)) same (adjacent or (close near6 proximit\$5) or abutt\$5) same (wafer or photoresist or substrate or photosensitive or sample)) and ((lens or (refractive near5 slab) or (projec\$5 near5 lens\$4 near4 element)) near29 ((refractive near6 index) or (index near4 refraction)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
6	2	430/396.ccls. and (((layout near8 object) or pattern\$4) same (mask\$3 or photomask or reticle)) and ((project\$4 near9 lens) same ((close near9 proximit\$4) or contact or vicinit\$3 or depress\$4 or touch\$3 or indent\$\$) same (sample or substrate or wafer or photosensitive or photoresist or resist)) and (expos\$4 or illumiant\$4 or irradiat\$4 or imag\$3) and ((lens or (refractive near26 slab) or (projection near6 lens near6 element)) same (adjacent or (close near6 proximit\$5) or abutt\$5) same (wafer or photoresist or substrate or photosensitive or sample)) and ((lens or (refractive near5 slab) or (projec\$5 near5 lens\$4 near4 element)) near29 ((refractive near6 index) or (index near4 refraction)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
7	6	430/311.ccls. and (((layout near8 object) or pattern\$4) same (mask\$3 or photomask or reticle)) and ((project\$4 near9 lens) same ((close near9 proximit\$4) or contact or vicinit\$3 or depress\$4 or touch\$3 or indent\$\$) same (sample or substrate or wafer or photosensitive or photoresist or resist)) and (expos\$4 or illumiant\$4 or irradiat\$4 or imag\$3) and ((lens or (refractive near26 slab) or (projection near6 lens near6 element)) same (adjacent or (close near6 proximit\$5) or abutt\$5) same (wafer or photoresist or substrate or photosensitive or sample)) and ((lens or (refractive near5 slab) or (projec\$5 near5 lens\$4 near4 element)) near29 ((refractive near6 index) or (index near4 refraction)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
8	2	<p>250/492.2.ccls. and  (((layout near8 object)  or pattern\$4) same  (mask\$3 or photomask or  reticle)) and  ((project\$4 near9 lens)  same ((close near9  proximit\$4) or contact  or vicinit\$3 or  depress\$4 or touch\$3 or  indent\$\$) same (sample  or substrate or wafer  or photosensitive or  photoresist or resist))  and (expos\$4 or  illumiant\$4 or  irradiat\$4 or imag\$3)  and ((lens or  (refractive near26  slab) or (projection  near6 lens near6  element)) same  (adjacent or (close  near6 proximit\$5) or  abutt\$5) same (wafer or  photoresist or  substrate or  photosensitive or  sample)) and ((lens or  (refractive near5 slab)  or (projec\$5 near5  lens\$4 near4 element))  near29 ((refractive  near6 index) or (index  near4 refraction)))</p>	<p>US-PGPUB;  USPAT; EPO;  JPO; DERWENT;  IBM_TDB</p>

	Hits	Search Text	DBs
9	7	(mask\$3 or photomask or reticle) and ((project\$4 near9 lens)) and (((final or bottom) near5 lens near6 element) same ((close near9 proximit\$4) or distance or adjacent) same (sample or substrate or wafer or photosensitive or photoresist or resist)) and (expos\$4 or illuminant\$4 or irradiat\$4 or imag\$3) and ((lens or (refractive near26 slab) or (projection near6 lens near6 element)) same (adjacent or (close near6 proximit\$5) or abutt\$5) same (wafer or photoresist or substrate or photosensitive or sample)) and ((lens or (refractive near5 slab) or (projec\$5 near5 lens\$4 near4 element)) near16 ((refractive near6 index) or (index near4 refraction)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB